

L Number	Hits	Search Text	DB	Time stamp
-	91	427/255.26.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 12:49
-	25	427/255.26.ccls. and diffuse	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 12:54
-	51	427/255.26.ccls. and diffus\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 12:54
-	15	427/255.26.ccls. and diffus\$6 near9 coat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 12:56
-	6	427/255.26.ccls. and diffus\$6 near9 contact	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 12:59
-	1	(427/255.26.ccls. and (plastic polymer\$3) near9 (substrate surface)) and diffus\$6 near9 contact	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:16
-	16	427/255.26.ccls. and (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:25
-	4	(427/255.26.ccls. and (plastic polymer\$3) near9 (substrate surface)) and vapo\$1r\$8 near9 coat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:19
-	5	(427/255.26.ccls. and (plastic polymer\$3) near9 (substrate surface)) and vapo\$1r\$8 near9 (coat\$3 modif\$8)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:20
-	1	(427/255.26.ccls. and (plastic polymer\$3) near9 (substrate surface)) and vapo\$1r\$8 near9 (monomer\$3 \$9silane \$5amine)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:24
-	2096	((chemical near3 vapo\$1r near3 deposition) CVD) same (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) and (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:27
-	372	((chemical near3 vapo\$1r near3 deposition) CVD) same (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) same (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:27

-	164	((chemical near3 vapo\$1r near3 deposition) CVD) near20 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) same (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:28
-	96	((chemical near3 vapo\$1r near3 deposition) CVD) near20 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near20 (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:28
-	57	((chemical near3 vapo\$1r near3 deposition) CVD) near10 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near10 (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:29
-	3	((chemical near3 vapo\$1r near3 deposition) CVD) near10 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near10 (plastic polymer\$3) near9 (substrate surface) near9 ((heat\$3 hot) (elevated raise\$3) near3 temperature))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:42
-	231	(react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) same (plastic polymer\$3) near9 (substrate surface) near9 flame	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:44
-	3770	(react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near9 (plastic polymer\$3) and flame	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:44
-	188	(react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near20 (plastic polymer\$3) near9 (substrate surface) near9 flame	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:46
-	4	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near20 (plastic polymer\$3) near9 (substrate surface) near9 flame	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:48
-	12	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) and (plastic polymer\$3) near9 (substrate surface) near9 (heat\$3 flame) near9 activat\$9	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:03
-	671	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) same (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 13:59
-	253	vapo\$1r\$7 near9 (covalent\$3 bond\$5 attach\$6 graft\$3) near9 (substrate surface) near9 (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:21
-	32	vapo\$1r\$7 near9 (covalent\$3 graft\$3) near9 (substrate surface) near9 (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:02
-	451	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5 attach\$6) near9 (substrate surface) same (plastic polymer\$3) near3 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:04

-	452	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5) near9 (substrate surface) near15 (plastic polymer\$3) near3 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:05
-	413	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5) near9 (substrate surface) near9 (plastic polymer\$3) near3 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:06
-	18	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5) near9 (substrate surface) near20 function\$9 near9 (plastic polymer\$3) near3 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:06
-	16	vapo\$1r\$7 near9 (react\$9 covalent\$3 bond\$5) near20 function\$9 near9 (plastic polymer\$3) near3 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:20
-	39	"5652021"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:20
-	17	"5652021" and (plastic polymer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:36
-	3	(FILIPPOU near3 CON).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:36
-	11	(GUTOWSKI near3 WOJCIECH).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:36
-	29	(PROCTOR near3 DAVID).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:37
-	7	(SPICER near3 MARK).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:37
-	42	((FILIPPOU near3 CON).in.) ((GUTOWSKI near3 WOJCIECH).in.) ((PROCTOR near3 DAVID).in.) ((SPICER near3 MARK).in.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:37
-	7	((((FILIPPOU near3 CON).in.) ((GUTOWSKI near3 WOJCIECH).in.) ((PROCTOR near3 DAVID).in.) ((SPICER near3 MARK).in.)) and vapo\$1r\$6 and modif\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:44
-	43	diffus\$8 near3 contact near9 vapo\$1r\$6 near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:48

-	10	diffus\$8 near contact near9 vapo\$1r\$6 near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:50
-	3042	diffus\$8 near9 vapo\$1r\$6 near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:52
-	132	(diffus\$8 near9 vapo\$1r\$6 near9 (substrate surface)) near9 chamber	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:51
-	1	(diffus\$8 near9 vapo\$1r\$6 near9 (substrate surface)) near9 chamber near3 enclosed	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:51
-	7	(diffus\$8 near9 vapo\$1r\$6 near9 (substrate surface)) near9 enclosed	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:52
-	188	diffus\$8 near9 vapo\$1r\$6 near9 (substrate surface) near9 cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:54
-	8	diffus\$8 near9 vapo\$1r\$6 near9 (substrate surface) near9 (react\$6 bond\$3) near3 (covalent\$3 chemically)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:57
-	0	diffus\$8 near3 contact near9 vapo\$1r\$6 near9 (\$9silane monomer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 14:58
-	21	diffus\$8 near9 vapo\$1r\$6 near9 (\$9silane monomer\$3) near9 (substrate surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 15:07
-	2	"5550001"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/27 15:07